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ABSTRACT OF THE DISCLOSURE

A corrected mask pattern verification apparatus includes a graphic operation section for generating differential mask pattern data based on design mask pattern and corrected mask pattern; a graphic reduction-enlargement operation section for reducing the differential mask pattern data and enlarging the reduced differential mask pattern data, and generating graphic reduction-enlargement operation data; and an area comparison operation section for calculating an area of a differential mask pattern represented by the differential mask pattern data and comparing the calculated area with a prescribed area, and generating area comparison operation data indicating an area comparison operation result.